



#7  
Amend A  
EOT (3)  
PATENT 88405.99R077  
Small  
7-12-01

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

Applicant:	Bruce W. Smith	)	Examiner:
		)	N. Nguyen
Application No.:	09/422,398	)	
		)	
Filing Date:	October 21, 1999	)	Art Unit:
		)	2851
For:	ILLUMINATION DEVICE FOR	)	
	PROJECTION SYSTEM AND METHOD	)	
	FOR FABRICATING	)	

AMENDMENT

Box: Non-Fee Amendment  
Assistant Commissioner for Patents  
Washington, DC 20231

Dear Sir:

In response to the office action mailed January 4, 2001, Applicant hereby submits the following amendment.

IN THE SPECIFICATION

On page 7, rewrite the paragraph beginning on line 21 as follows:

**Figure 4** is a plot of the x-y distribution of dithered bilevel masking cells for an illumination aperture consisting of four circular normal distributed-intensity zones placed at diagonal positions corresponding to off-axis illumination for geometry oriented in horizontal and vertical directions. The axes are divided into relative distances using the center and the edges of the mask.

On page 7, rewrite the paragraph beginning on line 33 as follows:

**Figure 7** is a plot of the x-y distribution of dithered, bilevel masking cells for an illumination aperture consisting of four elliptical normal distributed-intensity zones placed at diagonal positions corresponding to off-axis illumination for geometry oriented in horizontal and vertical directions. The axes are divided into relative distances using the center and the edges of the mask.